

On the experimental determination of f_{max}

A. Pawlak, M. Schröter

CEDIC, University of Technology Dresden, Germany

andreas.pawlak@tu-dresden.de

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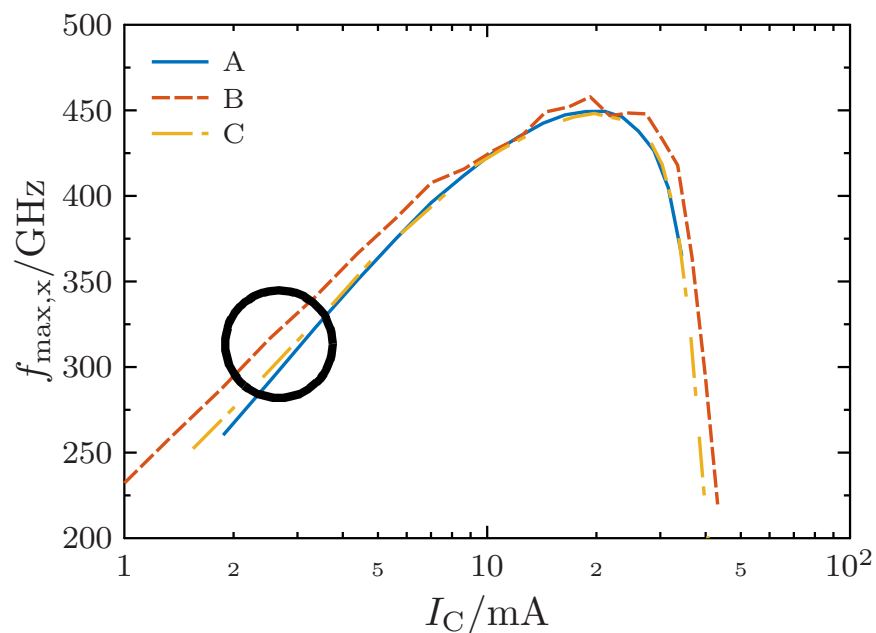
Overview

- Introduction
- Determination of f_{\max}
- Measurements of Y12
- Deembedding structures
- Comparison versus frequency
- Modeling point of view
- Comments on the calibration
- Conclusion

Introduction

measurements of f_{\max}

- Three measurement sites
 - same transistor on same wafer (although on different dies)
 - non-deembedded data



Determination of f_{\max}

- Calculation based on Mason's Unilateral Power Gain

$$U = \frac{|Y_{21} - Y_{12}|^2}{4(\Re\{Y_{11}\}\Re\{Y_{22}\} - \Re\{Y_{12}\}\Re\{Y_{21}\})}$$

$$f_{\max} = f\sqrt{U}$$

- Useful estimations

$$\Re\{Y_{12}\}\Re\{Y_{21}\} \gg \Re\{Y_{11}\}\Re\{Y_{22}\}$$

$$\Re\{Y_{21}\} \gg \Re\{Y_{12}\} \quad \text{and} \quad \Im\{Y_{21}\} \approx \Im\{Y_{12}\}$$

$$f_{\max} \approx \frac{f}{2} \sqrt{-\frac{\Re\{Y_{21}\}}{\Re\{Y_{12}\}}}$$

Measurements of Y_{12}

real part of small-signal parameters

$$f_{\max} \approx \frac{f}{2} \sqrt{-\frac{\Re\{\underline{Y}_{21}\}}{\Re\{\underline{Y}_{12}\}}}$$

- f_{\max} almost "only" depends on the real parts of \underline{Y}_{12} and \underline{Y}_{21}

$$\Re\{\underline{Y}\} = |\underline{Y}| \cos(\angle \underline{Y})$$

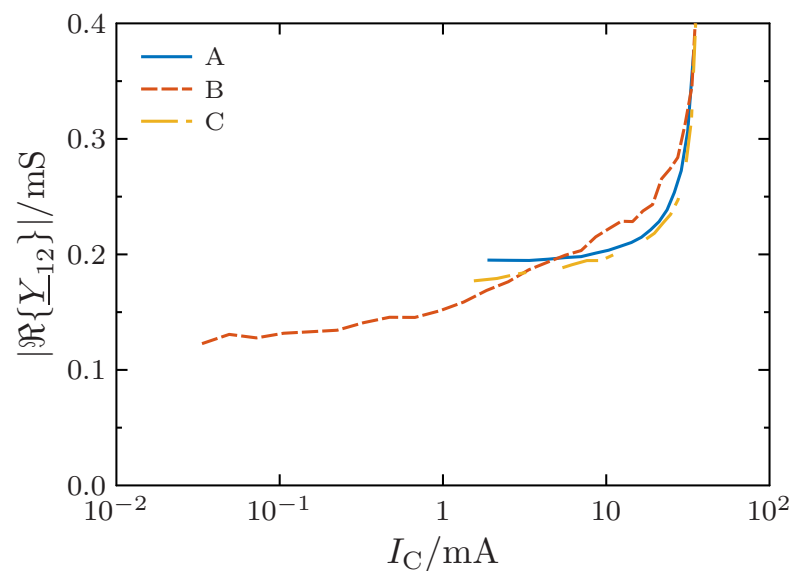
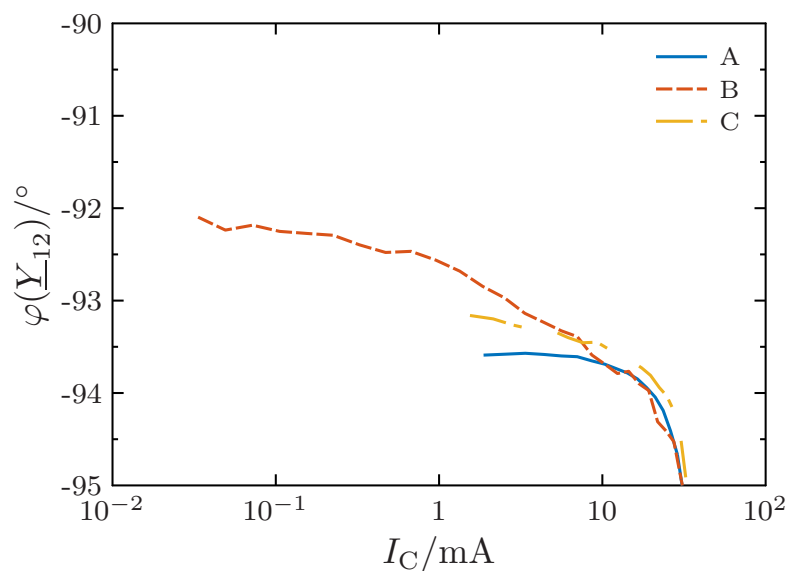
=> phase close to $n^*\pi$: weak dependence on phase (\underline{Y}_{21})

=> phase close to $(2n+1)/2^*\pi$: strong dependence on phase (\underline{Y}_{12})

Measurements of the phase

$$\Re\{\underline{Y}_{12}\} = |\underline{Y}_{12}| \cos(\angle \underline{Y}_{12})$$

- Different bias dependence of the measured phases



directly visible in the real part of \underline{Y}_{12} and thus f_{\max}
almost flat for A, increasing for B and C

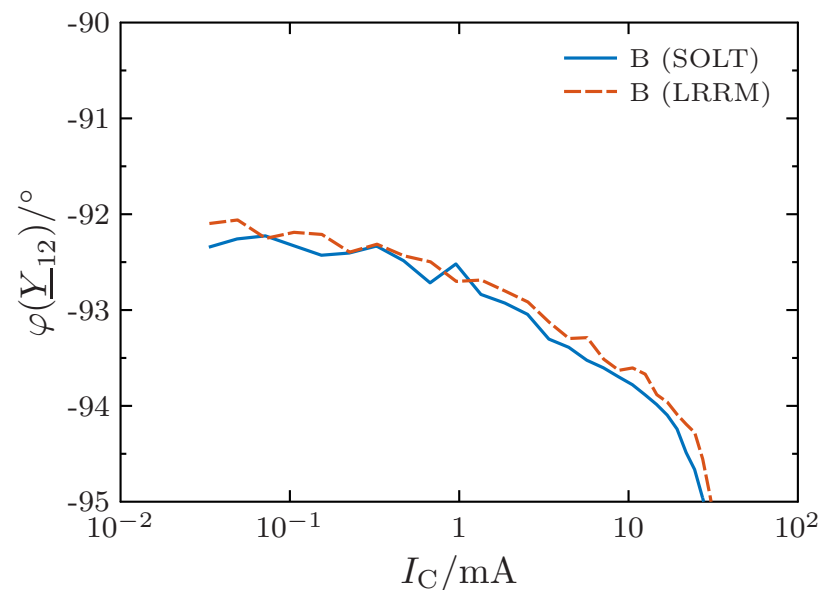
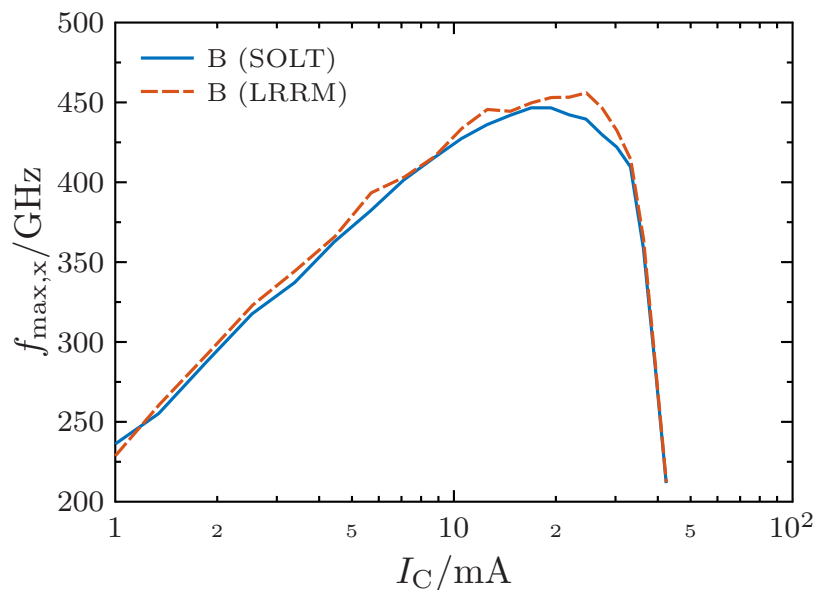
Possible causes of deviations

- Measurement setup
 - Probes
 - Cables
 - Bias-Tees
 - VNA (model and settings)
- Calibration
 - Routine
 - Results

Comparison of calibrations

SOLT vs. LRRM

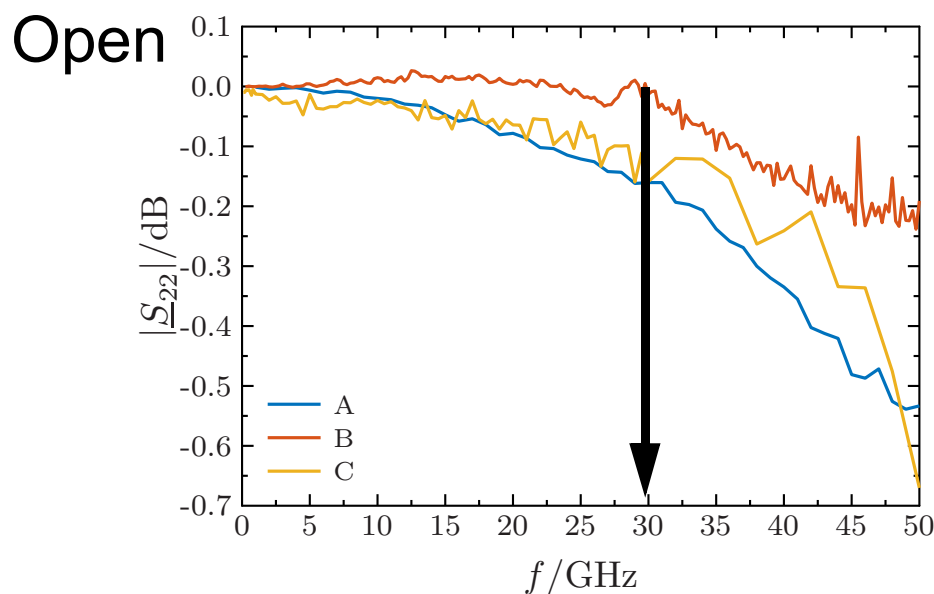
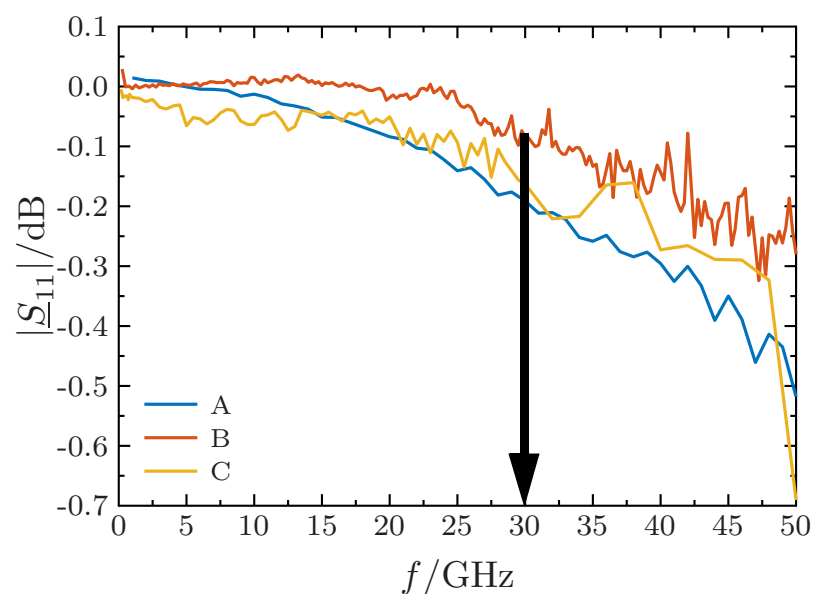
- LRRM less dependent on models for calibration standards



very similar results obtained for both methods

Deembedding structures

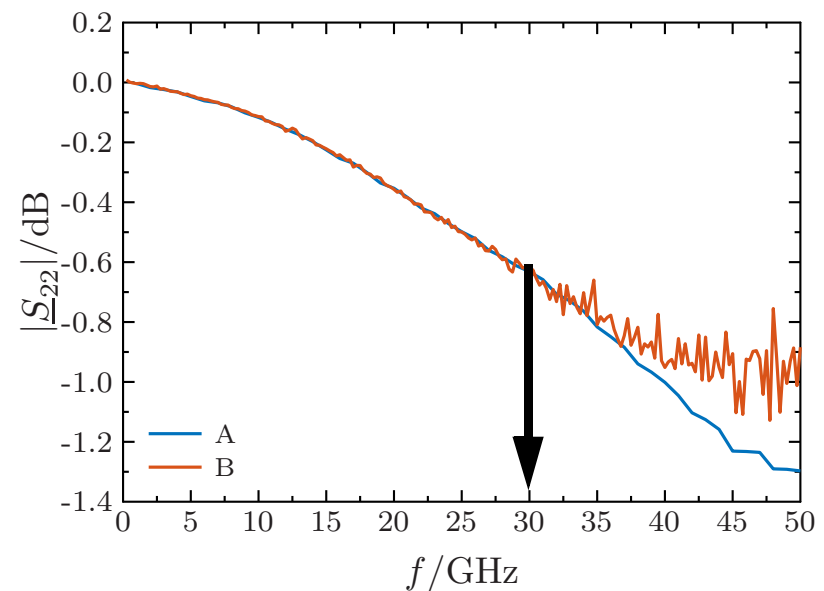
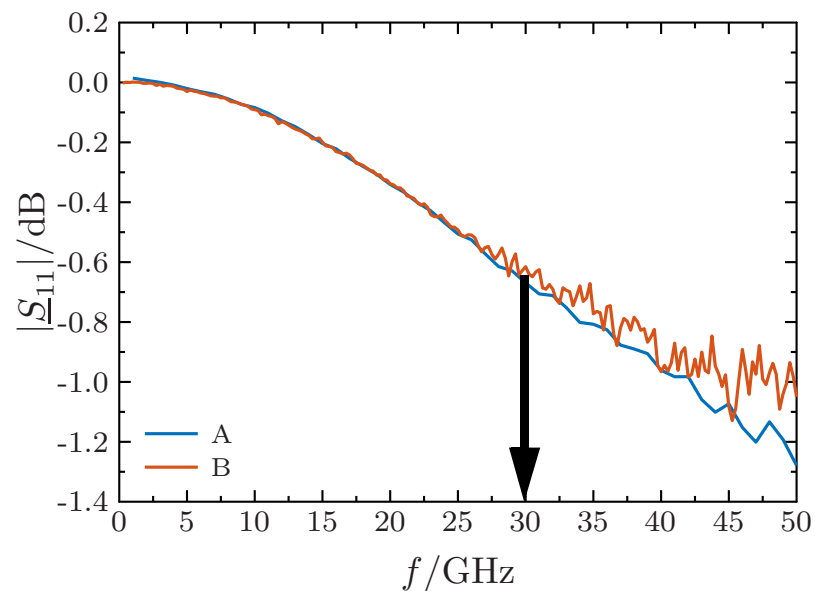
- "Simple" passive structures (open and short)
 - less sensitive to variations on the wafer
- Useful to compare calibrations



visible deviations in the reflection coefficients

Passive transistor

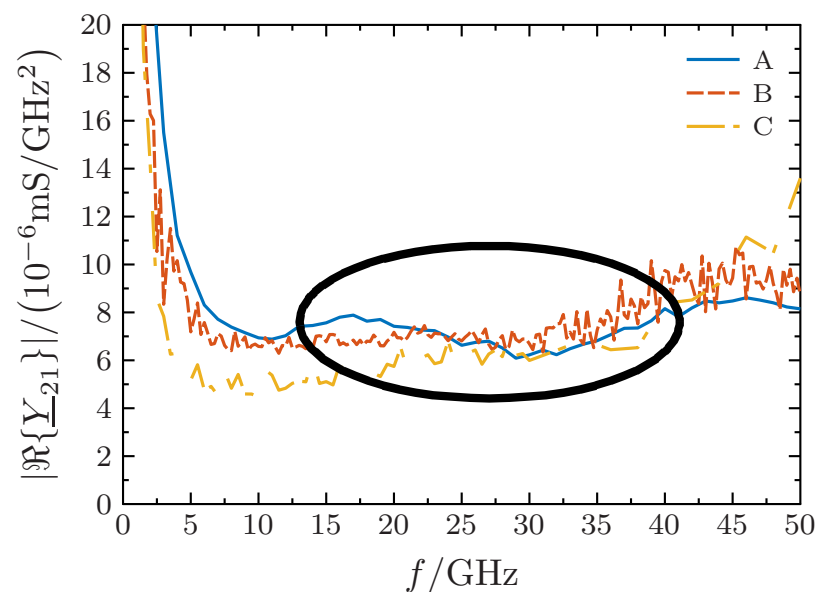
- Comparison of HBT at $V_{BE} = V_{BC} = 0$ V
similar characteristics as for the open



deviations at large frequencies

Comparison versus frequency

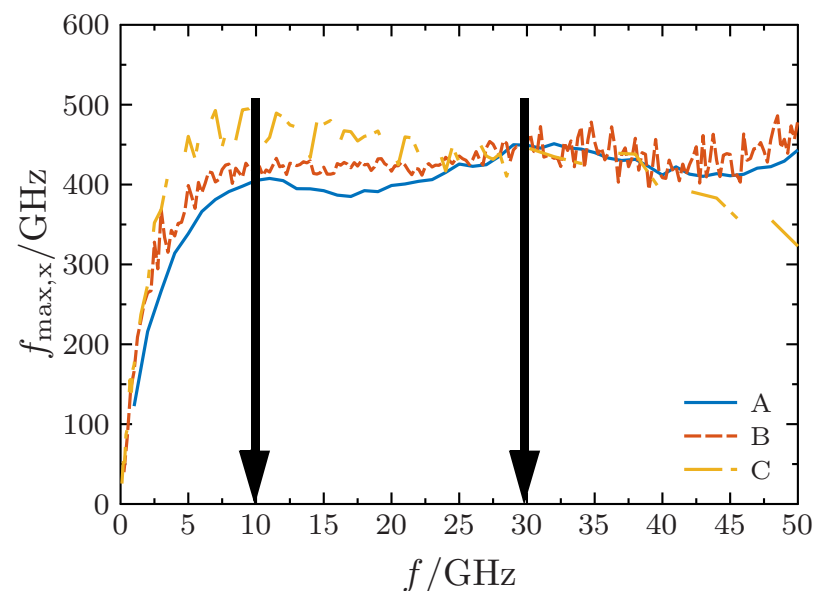
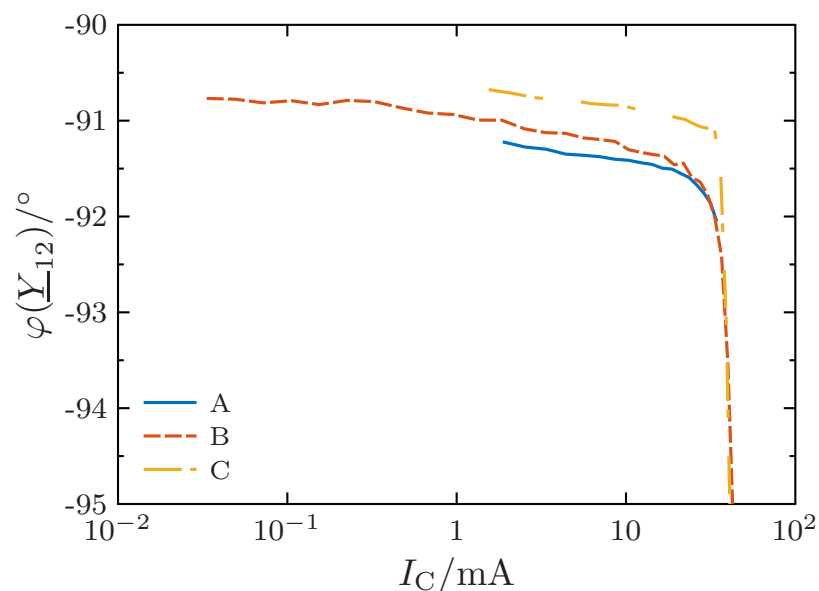
- Different frequency dependence of the S-parameter
- What does the frequency dependence of \underline{Y}_{12} look like?



valley for A exactly at reference extraction frequency

Comparison at small frequencies

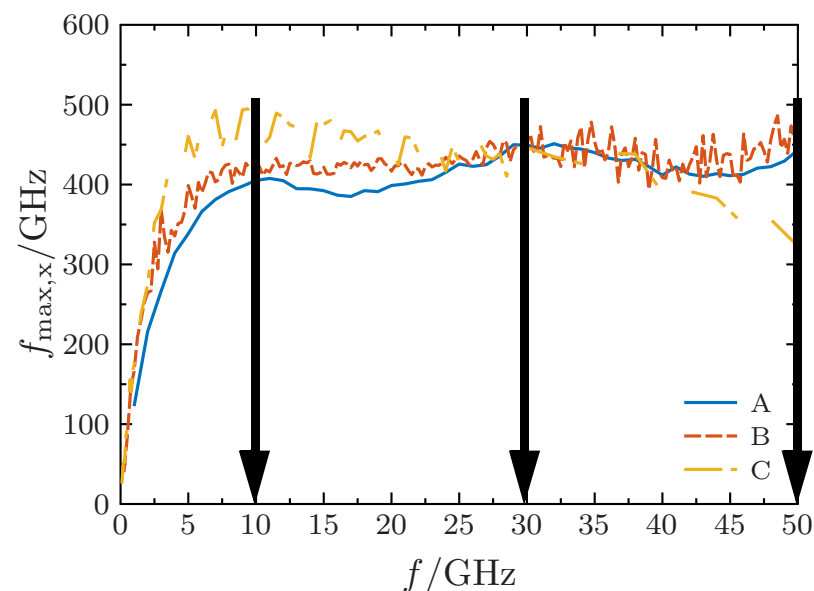
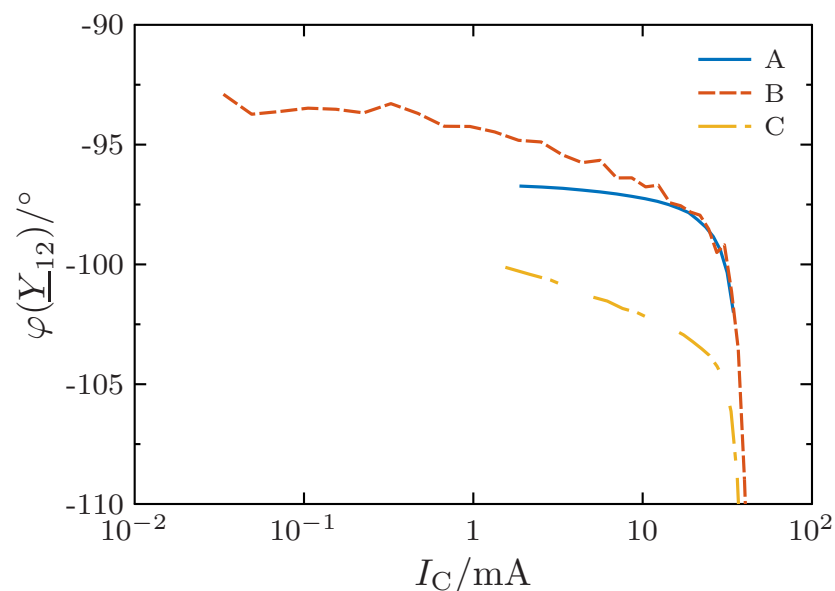
- Comparing results at 10 GHz
- similar results for all transistors



however, at small frequencies large differences
in the peak f_{\max}

Comparison at large frequencies

- Comparing results at 50 GHz
- similar results for all transistors

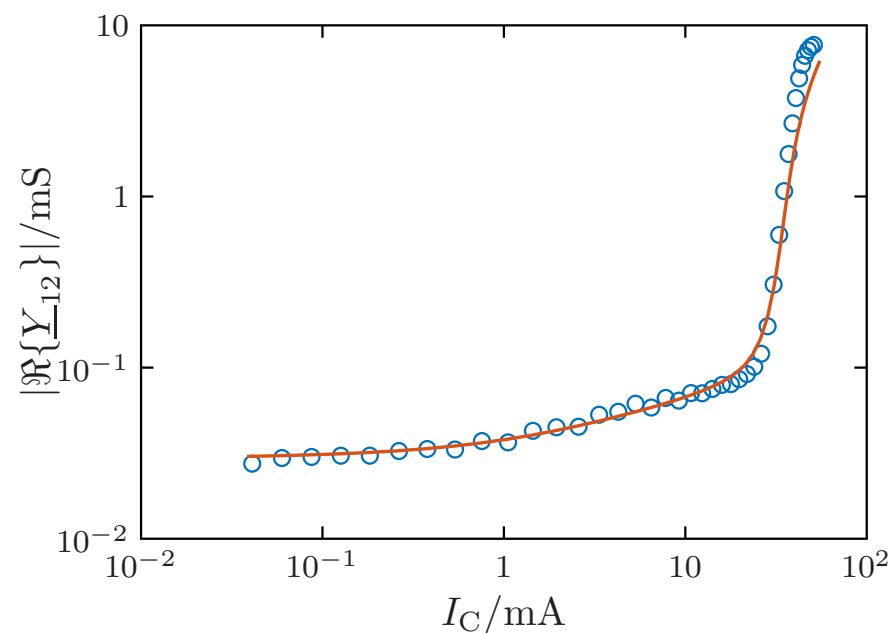
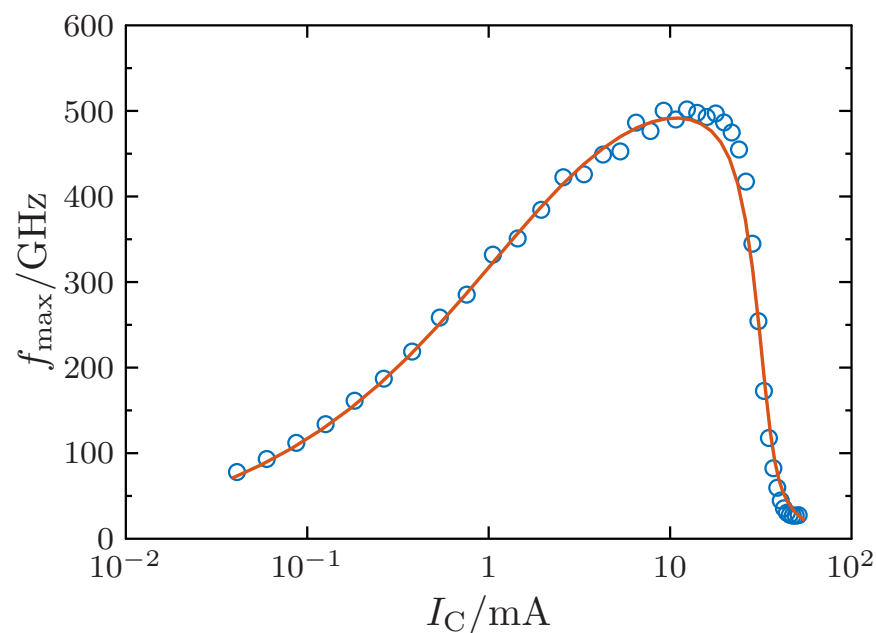


more reasonable bias dependence of A again
large differences of C to A and B (strongly reduced f_{\max})

Modeling point of view

What does the model predict and why?

- HICUM/L2 model



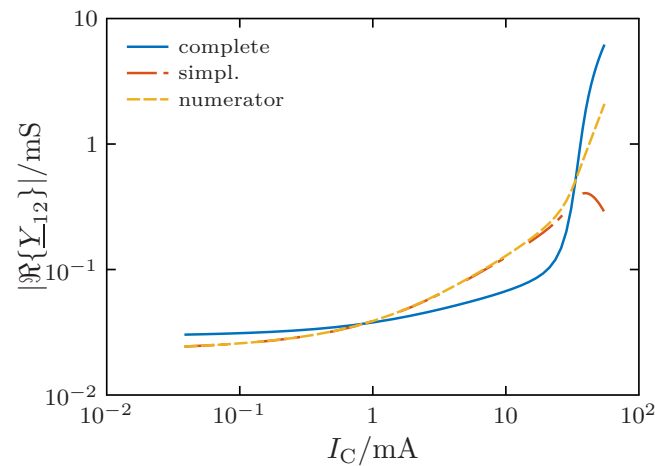
good agreement on both characteristics

Calculation of Y_{12}

- Simple assumptions

$$Y_{12} = \frac{Y_{12,i}}{1 + R_B Y_{11,i}}$$

$$\Re\{Y_{12}\} \approx -\frac{R_B \omega^2 C_{BC}(C_{BE} + C_{BC})}{1 + R_B^2 \omega^2 (C_{BE} + C_{BC})^2} \approx -R_B \omega^2 C_{BC}(C_{BE} + C_{BC})$$



Bias dependence

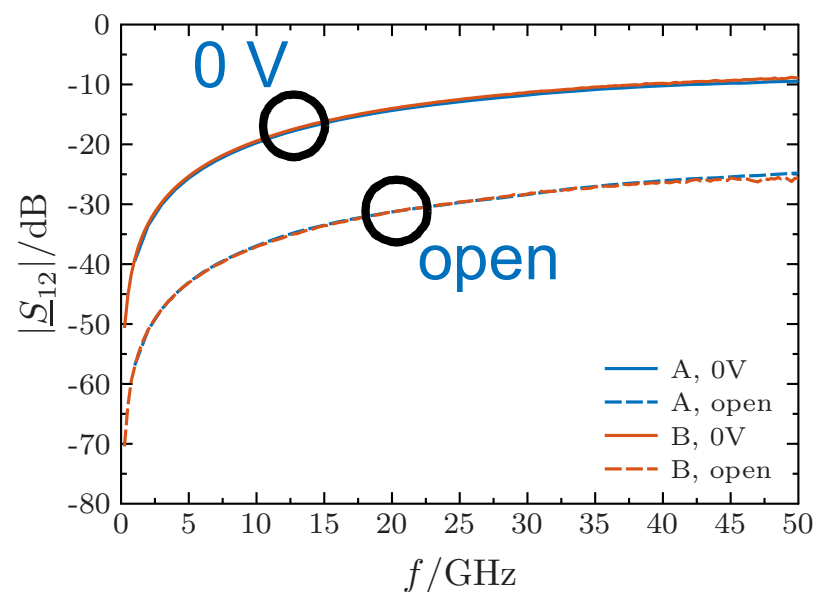
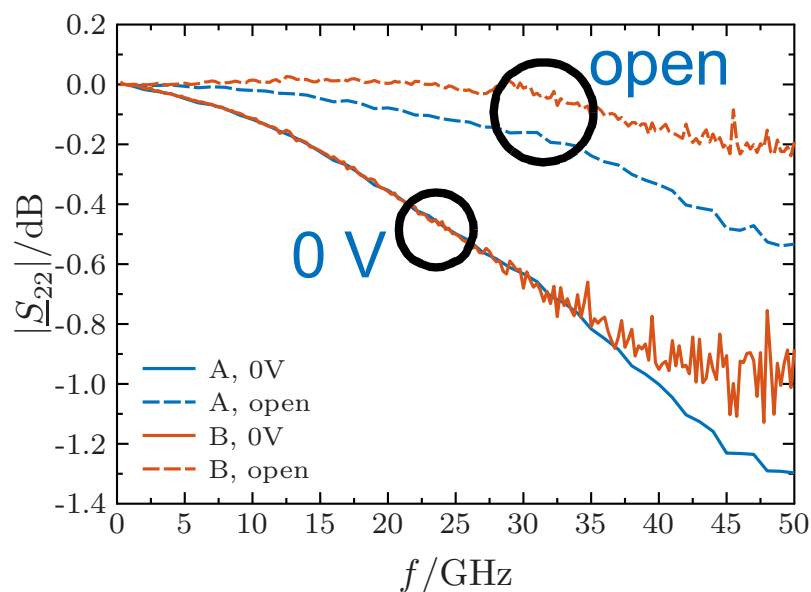
$$\Re\{\underline{Y}_{12}\} \approx -\frac{R_B \omega^2 C_{BC}(C_{BE} + C_{BC})}{1 + R_B^2 \omega^2 (C_{BE} + C_{BC})^2} \approx -R_B \omega^2 C_{BC}(C_{BE} + C_{BC})$$

- For both, V_{CE} and V_{BC} const. measurements
=> all capacitances increase with V_{BE}
- Base resistance decrease, but to a smaller extent
- Overall, $|\Re\{\underline{Y}_{12}\}|$ should increase as for *all* measurements at 10 GHz and 50 GHz and *some* at 30 GHz

Comments on the calibration

some more discussions on measured S-parameters

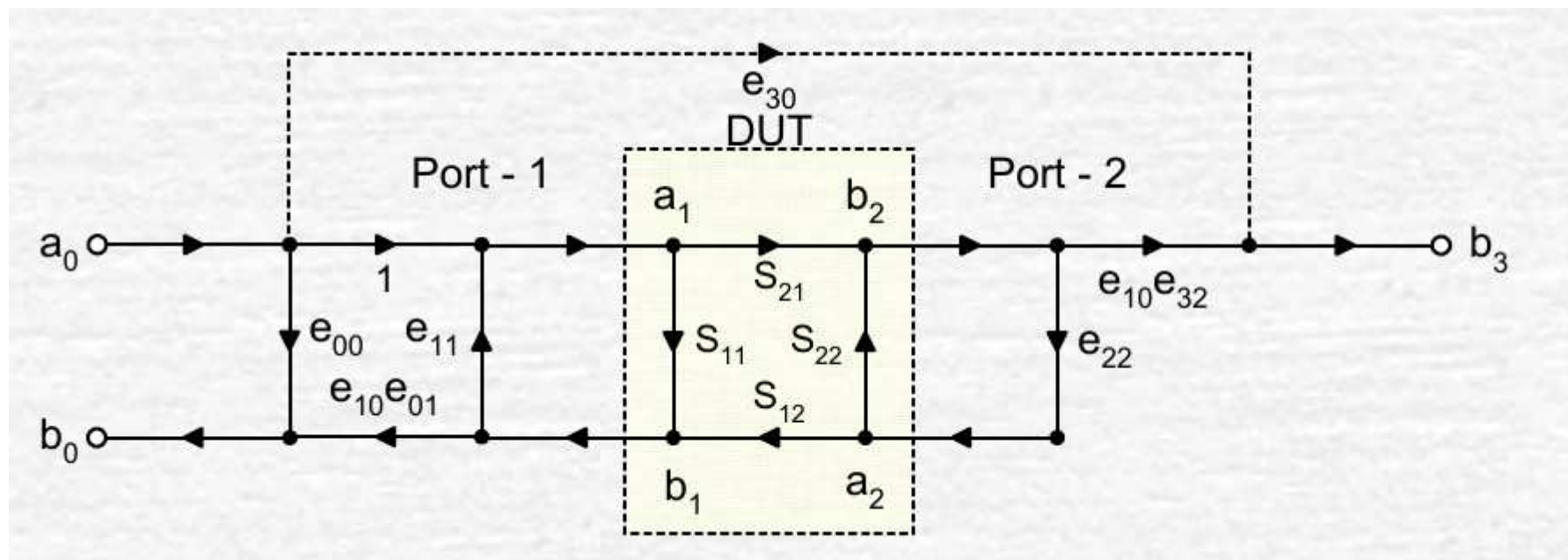
- Comparison of HBT 0 V and open measurements



deviations at different frequencies

Calculations

- Most measurements are with SOLT calibration



[Doug Rytting, "Network Analyzer Error Models and Calibration Methods"]

$$S_{11M} = \frac{b_0}{a_0} = e_{00} + (e_{10}e_{01}) \frac{S_{11} - e_{22}\Delta S}{1 - e_{11}S_{11} - e_{22}S_{22} + e_{11}e_{22}\Delta S}$$

Calculations

Open

- Very good isolations (< -30 dB)

$$|S_{11}S_{22}| \gg |S_{12}S_{21}|$$

$$S_{11M} \approx e_{00} + \frac{(e_{10}e_{01})S_{11}}{1 - e_{11}S_{11}}$$

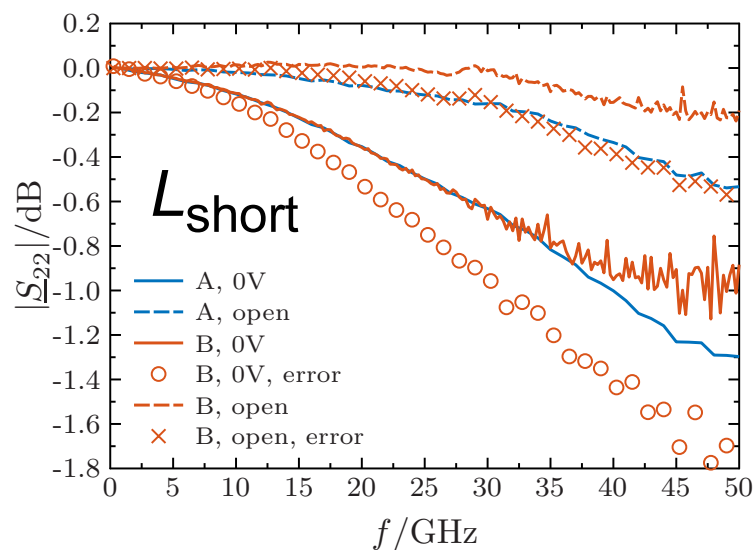
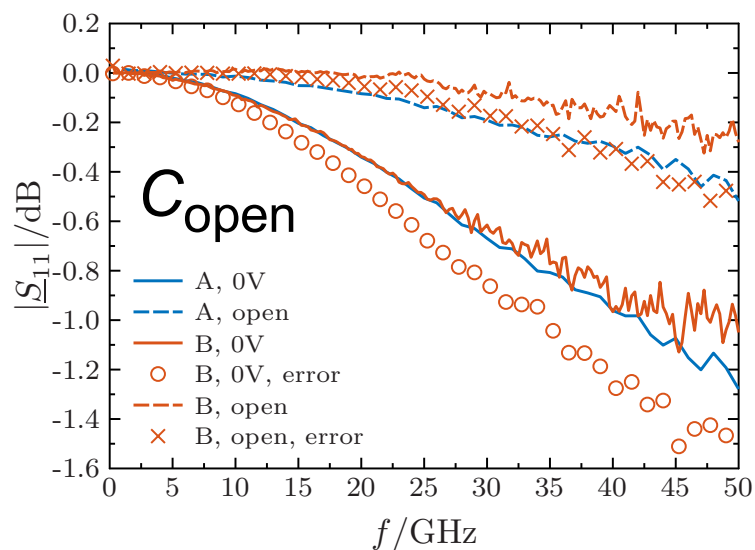
only one port SOL calibration to take into account for Open

Impact of calibration standards

- Procedure (full SOLT)
 - Calculate raw S-parameters of calibration standards with deviations in the Rs, Ls and Cs with reference error terms
 - Calculate new *erroneous* error terms
 - Calculate raw S-parameters of open and 0 V measurements using reference error terms
 - Calculated new S-parameters using *erroneous* error terms
- Parameters
 - C of open
 - L of short
 - R and L of load

Results

- Load:
 - L has on small impact
 - R has large impact but also on \underline{S}_{12} and \underline{S}_{21}
- Open and short
 - always impact on in the complete frequency range



Conclusion

- Difficulties to obtain consistent f_{\max} for the same transistor at different measurement sites
- Can be tracked back to deviations in the phase of \underline{Y}_{12}
- Physical and non-physical behavior strongly frequency dependent
- No simple explanation possible with calibration errors

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